L Number	Hits	Search Text	DB	Time stamp
1	29	silicon adj nitirde	USPAT;	2004/06/22 22:51
			US-PGPUB	
2	75787	silicon adj nitride	USPAT;	2004/06/22 22:51
			US-PGPUB	
3	5140	"Si.sub.3N.sub.4"	USPAT;	2004/06/22 22:51
			US-PGPUB	
4	1184	plasma adj (nitrid\$5 or nitrification or nitration)	USPAT;	2004/06/22 22:53
_			US-PGPUB	
5	88035	microwave\$1	USPAT;	2004/06/22 22:53
6	400400	abouted oil was a fit does at the control	US-PGPUB	0004/00/00 00 54
	103196	chemical adj vapor adj deposit\$3 or CVD	USPAT;	2004/06/22 22:54
7	2524	atomic adi layor adi denesit©2 ar ALD	US-PGPUB	2004/06/22 20:54
′	2024	atomic adj layer adj deposit\$3 or ALD	USPAT;	2004/06/22 22:54
8	3	((silicon adj nitride) or "Si.sub.3N.sub.4") same (plasma adj (nitrid\$5 or nitrification or	USPAT:	2004/06/22 23:15
	١	nitration)) same microwave\$1 same ((chemical adj vapor adj deposit\$3 or CVD) or (atomic	US-PGPUB	2004/00/22 23.13
		adj layer adj deposit\$3 or ALD))	0010100	
9	2	((silicon adj nitirde) or (silicon adj nitride)) same (remote adj plasma adj (chemical adj vapor	USPAT:	2004/06/22 23:04
	_	adj deposit\$3 or CVD)) same microwave\$1	US-PGPUB	200 1100 122 2010 1
10	0	((silicon adj nitirde) or (silicon adj nitride)) same (remote adj microwave\$1 adj (chemical adj	USPAT;	2004/06/22 23:03
		vapor adj deposit\$3 or CVD))	US-PGPUB	
11	215262	plasma	USPAT;	2004/06/22 23:03
		′	US-PGPUB	
12	11	((silicon adj nitirde) or (silicon adj nitride)) same (remote adj plasma adj (chemical adj vapor	USPAT;	2004/06/22 23:08
		adj deposit\$3 or CVD))	US-PGPUB	

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2004/06/22 23:08

2004/06/22 23:14

2004/06/22 23:16

((silicon adj nitirde) or (silicon adj nitride)) same microwave\$1

((silicon adj nitride) or "Si.sub.3N.sub.4") and ((plasma adj (nitrid\$5 or nitrification or

adj layer adj deposit\$3 or ALD)))
((silicon adj nitride) or "Si.sub.3N.sub.4") same (plasma adj (nitrid\$5 or nitrification or nitration)) same ((chemical adj vapor adj deposit\$3 or CVD) or (atomic adj layer adj

nitration)) same microwave\$1 same ((chemical adj vapor adj deposit\$3 or CVD) or (atomic

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deposit\$3 or ALD))